

(12) INTERNATIONAL APPLICATION PUBLISHED UNDER THE PATENT COOPERATION TREATY (PCT)

(19) World Intellectual Property
Organization
International Bureau

(43) International Publication Date
17 June 2021 (17.06.2021)



(10) International Publication Number
WO 2021/119485 A1

(51) International Patent Classification:

B24B 53/017 (2012.01) *H01L 21/687* (2006.01)
B24B 37/34 (2012.01)

(21) International Application Number:

PCT/US2020/064596

(22) International Filing Date:

11 December 2020 (11.12.2020)

(25) Filing Language:

English

(26) Publication Language:

English

(30) Priority Data:

201931051873 13 December 2019 (13.12.2019) IN

(71) Applicant: **LAM RESEARCH CORPORATION**
[US/US]; 4650 Cushing Parkway, Fremont, California
94538 (US).

(72) Inventors; and

(71) Applicants: **MCKINNEY, Robert** [US/US]; 4384 Cherrywood Avenue, Fremont, California 94538 (US). **KONDI, Sushanth** [IN/IN]; No: 22, 16th Cross, 8th Main, Malleswaram West, Bangalore 560055 (IN). **MANJUNATH, Mahendra Byrapura** [IN/IN]; No: 462, Bangalore 560098 (IN). **LIND, Gary B.** [US/US]; 13492 Lake Wildwood Drive, Penn Valley, California 95946 (US). **GULABAL, Vinayakaraddy** [IN/IN]; Yadgir 585291 (IN). **EIB, Andrew Paul** [US/US]; 781 Almondwood Way, San Jose, California 95120 (US). **OOI, Eddie Ze Thean** [MY/SG]; Blk 147 Lorong 2 Toa Payoh #07-340, 310147 (SG). **YALAMARTY, Vishnu Sai** [IN/SG]; 142 Lorong 2 Toa Payoh, 310142 (SG).

(74) Agent: **SCHEER, Bradley W.** et al.; Schwegman Lundberg & Woessner, P.A., P.O. Box 2938, Minneapolis, Minnesota 55402 (US).

(54) Title: PEDESTAL POLISHING APPARATUS

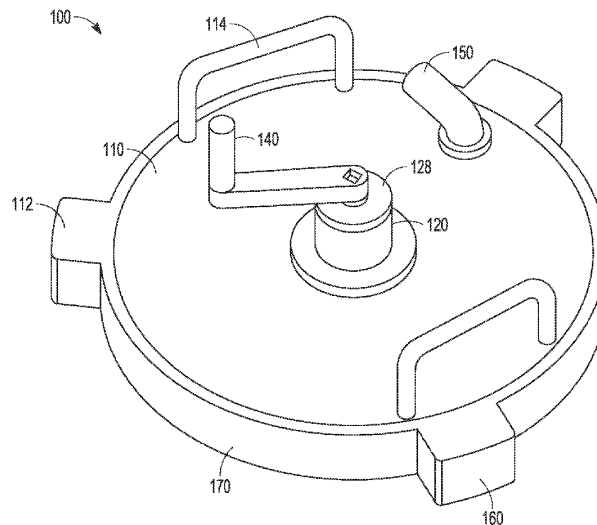


FIG. 1A

(57) Abstract: A cleaning apparatus for a vacuum pedestal and method of cleaning a pedestal used in semiconductor device fabrication are described. The apparatus has a baseplate, a collar attached to the baseplate, a cap disposed on the collar, and a shaft that extends from the collar through the cap, collar and baseplate. A manual rotatable handle is attached to a shaft portion that extends from the cap. Motion of the handle in a downward direction is impeded by the cap. A disk is attached to a lower portion of the shaft and is separated from a bottom of the baseplate due to weighted rings, which are attached to the disk and surround the lower portion of the shaft such that a vertical float is present between the shaft and the cap. At least one abrasive pad is attached to the disk to remove build-up on the underlying pedestal surface.

[Continued on next page]

WO 2021/119485 A1

(81) Designated States (*unless otherwise indicated, for every kind of national protection available*): AE, AG, AL, AM, AO, AT, AU, AZ, BA, BB, BG, BH, BN, BR, BW, BY, BZ, CA, CH, CL, CN, CO, CR, CU, CZ, DE, DJ, DK, DM, DO, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, GT, HN, HR, HU, ID, IL, IN, IR, IS, IT, JO, JP, KE, KG, KH, KN, KP, KR, KW, KZ, LA, LC, LK, LR, LS, LU, LY, MA, MD, ME, MG, MK, MN, MW, MX, MY, MZ, NA, NG, NI, NO, NZ, OM, PA, PE, PG, PH, PL, PT, QA, RO, RS, RU, RW, SA, SC, SD, SE, SG, SK, SL, ST, SV, SY, TH, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, WS, ZA, ZM, ZW.

(84) Designated States (*unless otherwise indicated, for every kind of regional protection available*): ARIPO (BW, GH, GM, KE, LR, LS, MW, MZ, NA, RW, SD, SL, ST, SZ, TZ, UG, ZM, ZW), Eurasian (AM, AZ, BY, KG, KZ, RU, TJ, TM), European (AL, AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HR, HU, IE, IS, IT, LT, LU, LV, MC, MK, MT, NL, NO, PL, PT, RO, RS, SE, SI, SK, SM, TR), OAPI (BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, KM, ML, MR, NE, SN, TD, TG).

Published:

— with international search report (Art. 21(3))